

How long is ten years?

Ten years is the age of JM³ as well as the tenure of this founding editor-in-chief. It is short in terms of the vivid memory of the early days but is long as far as volumes and issues are concerned. I accepted the challenge in April 2001. The inaugural issue appeared in April 2002. Since then, there have been 10 volumes and 39 issues containing, as of this writing, an estimated total of 722 articles spanning about 5800 pages. Approximately 2647 authors will have published their articles in JM³ by the end of 2011. The editorial board started with three senior editors. Currently, there are four senior editors in the disciplines of micro/nanolithography, MEMS, MOEMS, and microfabrication. There have been 66 associate editors, 28 of whom stepped down from the editorial board, as well as three senior editors, whom stepped down after their terms expired. Nearly 1000 reviewers provided their valuable opinions. We are extremely indebted to them. We appreciate the tremendous support given by SPIE, the publications committee, and the helpful staff members. Among them, Eric Pepper, Harry Levinson, and Karolyn Labes have given special attention to JM³.

The journal started with the name *Journal of Microlithography, Microfabrication, and Microsystems*. To more accurately reflect its coverage, the name was changed to the *Journal of Micro/Nanolithography, MEMS, and MOEMS* in 2007, even though its abbreviation remains JM³.

We experienced an impact factor drop in 2009. Due to an administrative misunderstanding between SPIE and Thomson Reuters that caused a delay in the indexing of the *Proceedings of SPIE*, the impact factors of all optics-related journals decreased in 2009, with JM³ experiencing one of the most severe hits. Fortunately, it is now restored.

The succeeding editor-in-chief is Dr. Chris Mack, who is well known in the lithography community. You are referred to my July-September 2011 editorial for an introduction of him.

Early in the past ten years, I have experienced the introduction of the 130-nm semiconductor logic node into high-volume manufacturing. Five generations later, we are now experiencing the introduction of the 28-nm logic node into high-volume manufacturing. MEMS and MOEMS have not slowed down either. They also experienced much innovation and improved sophistication. Technology always needs more innovation and dedication to be sustainable. I expect this growth to continue.

In addition to editing JM³, I filled the past decade with exciting work, such as the introduction of immersion lithography, managing a team of 50 grown into 350 people, winning some awards and recognition, and authoring a book, a book chapter, 67 articles, and 42 patents. Work is more exciting than ever. Retirement is still beyond grasp. However, it is time to pass the baton of JM³ to a well-qualified successor.

Happy reading!

Burn J. Lin

Editor-in-Chief

